

3 2
19. The polishing pad of claim 18, wherein the transparent section extends through the first layer.

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20. The polishing pad of claim 18, wherein the aperture extends through the second layer.

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21. The polishing pad of claim 17, wherein the transparent section and the aperture have substantially the same dimension.

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22. The polishing pad of claim 17, wherein a top surface of the transparent section is substantially coplanar with the polishing surface.

23. A polishing pad for a chemical mechanical polishing apparatus, comprising:
a first layer having a polishing surface and a transparent section; and
a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section.

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24. The polishing pad of claim 23, wherein the first layer is formed of a polyurethane material.

25. The polishing pad of claim 25, wherein the transparent section is formed of a polyurethane material.

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26. The polishing pad of claim 23, wherein the second layer is a backing layer.

27. A polishing pad for a chemical mechanical polishing apparatus, comprising:

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an article having a polishing surface and a substantially transparent section, the transparent section having a first portion with a first dimension and a second portion with a second, different dimension.

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28. The polishing pad of claim 27, wherein the article includes a first layer with the polishing surface and a second layer adjacent to the first layer.

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29. The polishing pad of claim 28, wherein the transparent section extends through the first and second layers.

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30. The polishing pad of claim 29, wherein the first section of the aperture extends through the first layer and the second section of the aperture extends through the second layer.

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31. A chemical mechanical polishing apparatus, comprising:
a carrier head to hold a substrate;
a polishing pad having a polishing surface and a surface opposite the polishing surface, the polishing pad including a first layer having a polishing surface with a transparent section and a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section; and
a motor to generate relative motion between the carrier head and the polishing pad.

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32. The apparatus of claim 31, further comprising a platen to support the polishing pad.

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AL 33. The apparatus of claim 32, wherein the second layer abuts the platen.

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AL 34. The apparatus of claim 33, wherein a passage is formed in the platen, and the passage is substantially aligned with the aperture in the polishing pad.

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